	Hit s	Search Text	DBs
34	1	photolithograph\$4 or projection)) or (project\$3 near4 (apparatus or system or align\$4) near5 (immers\$4 or liquid)	
35	1	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable)) and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((immers\$5 near9 (lithograph\$4 or photolithograph\$4 or projection)) or	US-PGPUB



	Hit s	Search Text	DBs
3 6	1	or align\$4) near5 (immers\$4 or liquid)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
37	1	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable)) and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((immers\$5 near9 (lithograph\$4 or photolithograph\$4 or projection)) or (project\$3 near4 (apparatus or system	US-PGPUB